



PATENT  
Customer No. 22,852  
Attorney Docket No. 07303.0031

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )  
)  
Bausan YUAN et al. )  
)  
Application No.: 09/759,524 ) Group Art Unit: 2851  
)  
Filed: January 16, 2001 ) Examiner: Peter Kim  
)  
For: REACTION MASS FOR A STAGE )  
DEVICE )

Commissioner for Patents  
Washington, DC 20231

Sir:

AMENDMENT

In reply to the Office Action dated December 4, 2002, the period for response to which having been extended to May 4, 2003 by petition and payment of requisite fee filed herewith, please amend this application as follows:

IN THE SPECIFICATION:

Page 12, please amend the paragraph beginning with "In accordance with" and bridging pages 12 and 13 to read as follows:

In accordance with Newton's third law, stage force  $F_{in}$  acts in an equal magnitude but in opposite directions on stage 201 and base 202. Whatever motion stage 201 makes, base 202 will make the exact opposite motion scaled by the ratio of masses between stage 201 and base 202. In the photolithography system, generally base 202 weighs more than stage 201. Generally, stage 201 and base 202 move synchronously

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